

## PATENT ABSTRACTS OF JAPAN

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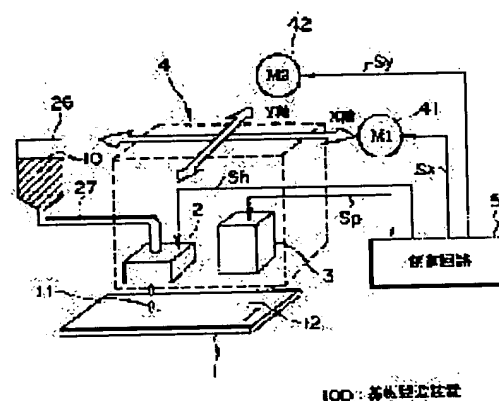
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## (54) METHOD OF FORMING PATTERN AND DEVICE FOR MANUFACTURING SUBSTRATE

## (57)Abstract:

**PROBLEM TO BE SOLVED:** To provide a manufacturing technology for a substrate for forming a pattern on a substrate by the use of an ink jet system.

**SOLUTION:** A substrate manufacturing device is provided for forming an arbitrary pattern on a substrate 1 by a fluidized body 11. This device is provided with an ink jet type recording head 2, which is constituted so that the fluidized body 11 can be projected on a substrate 1, processing means 3 for operating a constant processing on the substrate 1, drive means 4 for changing the relative position of the ink jet type recording head 2 and the processing means 3 to the substrate 1, and control means 5 for controlling the projection of the fluidized body 11 from the ink jet type recording head 2, the processing by the processing means 3, and the driving by the driving means 4. The control means is constituted capable of controlling the processing means to executing the processing, prior to the projection of the fluidized body from the ink jet type recording head 2.



100: 基板上に形成

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